

WHAT IS CLAIMED IS:

1 1. A bubble-jet type ink jet printhead, comprising:
2 a substrate integrated with a manifold for supplying ink and an ink chamber connected with
3 the manifold for containing ink to be ejected, said manifold and said ink chamber being are recessed
4 from the same surface of the substrate;
5 a nozzle plate located on a top surface of said substrate to cover the manifold and the ink
6 chamber, said nozzle plate being perforated by a nozzle hole located directly above a center portion
7 of said ink chamber;
8 a heater surrounding the nozzle hole on the nozzle plate; and
9 electrodes electrically connected with the heater for applying current to the heater, wherein
10 said ink chamber is substantially concave.

1 2. The printhead of claim 1, wherein said ink chamber is substantially hemispherical.

1 3. The printhead of claim 2, further comprising an ink channel located between said
2 manifold and said ink chamber, said ink channel connecting said manifold with said ink chamber,
3 said ink channel is recessed from the same surface of the substrate to be integrated with the substrate.

1 4. The printhead of claim 3, wherein said ink channel is shallower than said ink chamber.

1 5. The printhead of claim 3, further comprising a bubble keeping portion projecting higher

2 than a bottom of said ink channel where said ink channel joins said ink chamber.

1 6. The printhead of claim 1, wherein the ink chamber has a elliptic cross section, and one
2 side of the semimajor axis intercepts said manifold.

1 7. The printhead of claim 6, wherein said heater is elliptic in shape, conforming to the shape
2 of the ink chamber having a elliptic cross section.

1 8. The printhead of claim 1, wherein the nozzle plate comprises:
2 an insulating layer covering said substrate, wherein an opening for an ink chamber and an
3 opening for said manifold are formed at positions corresponding to the center portion of the ink
4 chamber and said manifold, respectively; and
5 a protective layer covering said insulating layer and covering said opening of said manifold,
6 said protective layer having an opening above said ink chamber serving as said nozzle hole for said
7 printhead.

1 9. The printhead of claim 8, wherein said protective layer is comprised of a polyimide
2 film.

1 10. The printhead of claim 1, further comprising a bubble guide and a droplet guide, said
2 droplet guide being an extension of said nozzle hole with walls extending towards a bottom surface

3 of said ink chamber, said bubble guide being a gap in said substrate near said heater and exterior to
4 said droplet guide, providing a space for a bubble to grow inside said ink chamber.

1 11. The printhead of claim 1, wherein the heater is "C" shaped and the electrodes are
2 coupled to both ends of the "C" shaped heater, respectively.

1 12. The printhead of claim 2, wherein the heater is "O" shaped and the electrodes are
2 electrically coupled to two diametrically opposite points of said "O" shaped heater, respectively.

1 13. A method of manufacturing a bubble-jet type ink jet printhead, the method
2 comprising the steps of:

3 forming an insulating layer on the surface of a substrate;

4 forming a round-shaped heater on the insulating layer;

5 forming electrodes electrically connected with the round-shaped heater on the insulating
6 layer;

7 etching said insulating layer to form a opening for an ink chamber and an opening for a
8 manifold, said opening for said ink chamber having a diameter less than that of said round-shaped
9 heater and being located inside said round-shaped heater, said opening for said manifold being
10 located outside said round-shaped heater;

11 etching said substrate using said insulating layer having said openings as an etch mask to
12 form an ink chamber having a diameter greater than that of the round-shaped heater wherein said ink

13 chamber resulting in a concave shape, and said manifold; and
14 depositing a protective layer over said insulating layer, said protective layer covering said
15 opening for said manifold, said protective layer being perforated by a hole, said hole overlapping
16 said opening in said insulating layer for said ink chamber producing a nozzle hole.

1 14. The method of claim 13, wherein the step of etching the substrate comprises the steps
2 of:
3 performing an anisotropic etch on said substrate to a predetermined depth using the insulating
4 layer in which said opening for an ink chamber and said opening for a manifold as an etch mask; and
5 performing an isotropic etch on the substrate.

1 15. The method of claim 13, wherein, said step of etching said insulating layer achieves
2 an opening in said insulating layer that is wider than said resulting manifold while said opening in
3 said insulating layer is entirely outside said heaters, allowing said step of etching said substrate to
4 produce an ink channel in addition to a manifold and ink chamber, said ink channel connecting said
5 ink chamber with said manifold as said substrate from said ink chamber through to said manifold
6 is recessed as a result of said etching step.

1 16. The method of claim 15, wherein said opening in said insulating layer for said ink
2 chamber is elliptic.

1 17. The method of claim 15, wherein said opening in said insulating layer for said ink
2 chamber is circular.

1 18. The method of claim 13, between the steps of etching the insulating layer and etching
2 the substrate, further comprising the steps of:

3 forming an etch mask exposing said opening for an ink chamber on the insulating layer;
4 performing an anisotropic etch on the substrate exposed by the etch mask and the insulating
5 layer by a predetermined depth to form a hole;
6 removing the etch mask; and
7 forming a spacer along a sidewall of the hole.

1 19. The method of claim 13, wherein the substrate is comprised of silicon.

1 20. The method of claim 19, wherein the insulating layer is formed by oxidizing the
2 surface of the silicon substrate.

1 21. The method of claim 13, wherein the heater is comprised of either polycrystalline
2 silicon doped with impurities or a Ta-Al alloy.

1 22. The method of claim 13, wherein the protective layer is comprised of a polyimide
2 film.